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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Kazuo ICHIKAWA et al.

Group Art Unit: 1763

Application No.: 09/670,877

Examiner: R. Zervigon

Filed: September 27, 2000

Docket No.: 107469

For: CVD SUBSTRATE AND CLEANING METHOD

**REQUEST FOR RECONSIDERATION**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In reply to the May 19, 2004 Office Action, the period for response being extended by the enclosed Petition for Extension of Time, reconsideration of the rejection is respectfully requested in view of the following remarks. Claims 1-6 are pending, and claims 3 and 4 are withdrawn from consideration.

**I. The Claims Define Patentable Subject Matter**

The Office Action rejects claims 1, 2, 5 and 6 under 35 U.S.C. §103(a) over Hara (U.S. Patent No. 5,648,276) in view of Babayan (U.S. Patent Publication No. 2002/0129902 A1). The rejection is respectfully traversed.

In particular, neither Hara nor Babayan discloses or suggests radicals in a plasma are introduced into a film deposition chamber from the plasma generator through introduction holes of a lower plate... the lower plate is connected to ground, as recited in independent claims 1 and 5. Moreover, neither Hara nor Babayan discloses or suggests each of the introduction holes is designed to pass the radicals only to the film deposition chamber, as